

L Number	Hits	Search Text	DB	Time stamp
1	3	(grating same interfer\$) same (overlay same latent)	USPAT; US-PGPUB	2004/08/18 17:22
2	10	(grating same interfer\$) and (overlay same latent)	USPAT; US-PGPUB	2004/08/18 17:22
3	101	((356/508,509,496).CCLS.) and ((mask reticle photomask reticule) same (substrate wafer semiconduct\$))	USPAT	2004/08/18 17:22
4	117	((356/508,509,496).CCLS.) and ((mask reticle photomask reticule) same (substrate wafer semiconduct\$))	USPAT; US-PGPUB	2004/08/18 17:22
5	343	((align\$ same mask) same (wafer substrate semiconduct\$)) and ((imag\$3 project\$ expos\$3) same (overlay same (resist photoresist)))	USPAT; US-PGPUB	2004/08/18 17:23
6	2234	(356/399-401).CCLS.	USPAT; US-PGPUB	2004/08/18 17:23
7	3204	(355/53,55).CCLS.	USPAT; US-PGPUB	2004/08/18 17:23
8	5370	(430/5,22,30).CCLS.	USPAT; US-PGPUB	2004/08/18 17:23
9	996	(250/548).CCLS.	USPAT; US-PGPUB	2004/08/18 17:23
10	166	((356/399-401).CCLS.) and (overlay same (grating mark\$ target))	USPAT; US-PGPUB	2004/08/18 17:23
11	123	((355/53,55).CCLS.) and (overlay same (grating mark\$ target))	USPAT; US-PGPUB	2004/08/18 17:23
12	206	((430/5,22,30).CCLS.) and (overlay same (grating mark\$ target))	USPAT; US-PGPUB	2004/08/18 17:23
13	35	((250/548).CCLS.) and (overlay same (grating mark\$ target))	USPAT; US-PGPUB	2004/08/18 17:24